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Supporting Information

for *Small*, DOI: 10.1002/smll.201302397

**Multi-Temperature Zone, Droplet-based Microreactor for
Increased Temperature Control in Nanoparticle Synthesis**

E. Yegân Erdem, Jim C. Cheng, Fiona M. Doyle, and Albert
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Supporting Information

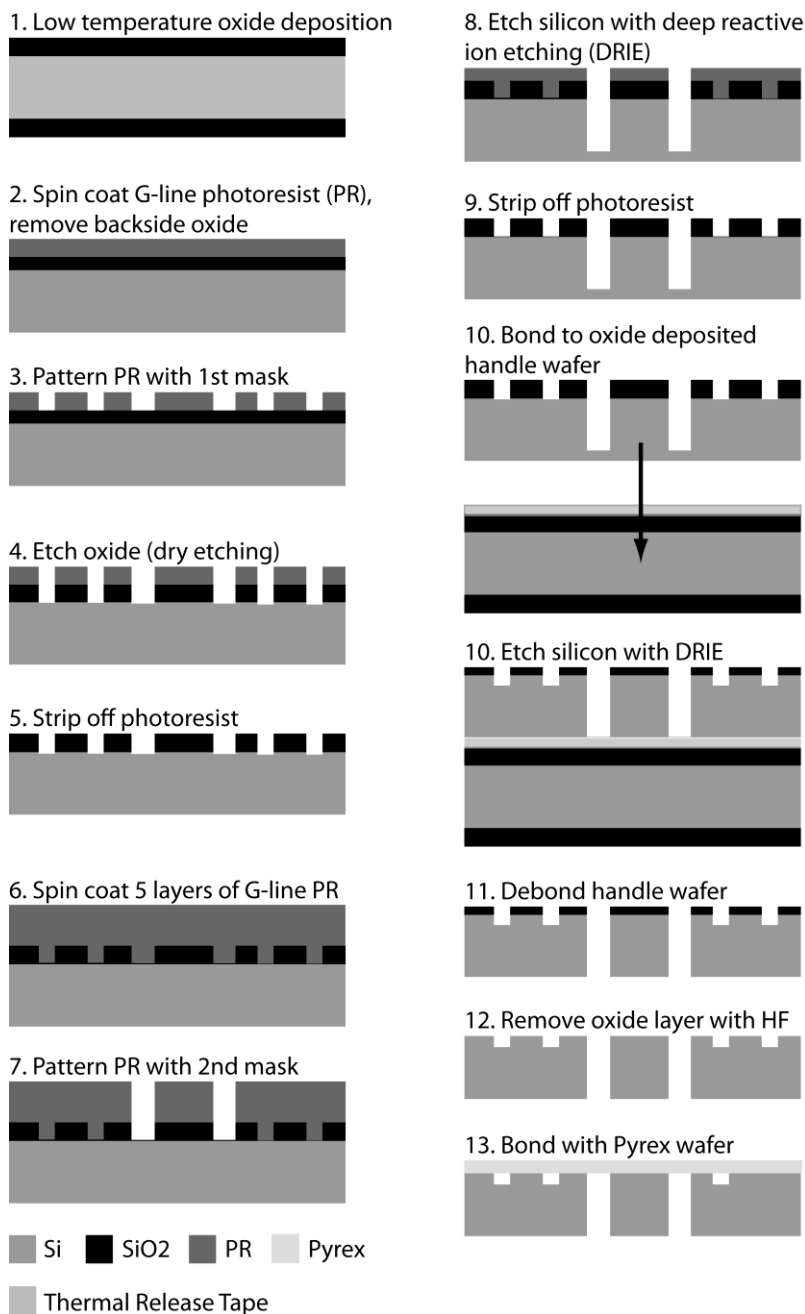
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Figure S1. Schematic of the fabrication steps of the microreactor. Two photo masks were used during the fabrication. The first mask defines the channel geometry and the second mask defines the thermal isolation. A handle wafer is used at the final step of DRIE in order to prevent harm to the etching tool. The handle wafer is removed via heating after the end of the etching process.

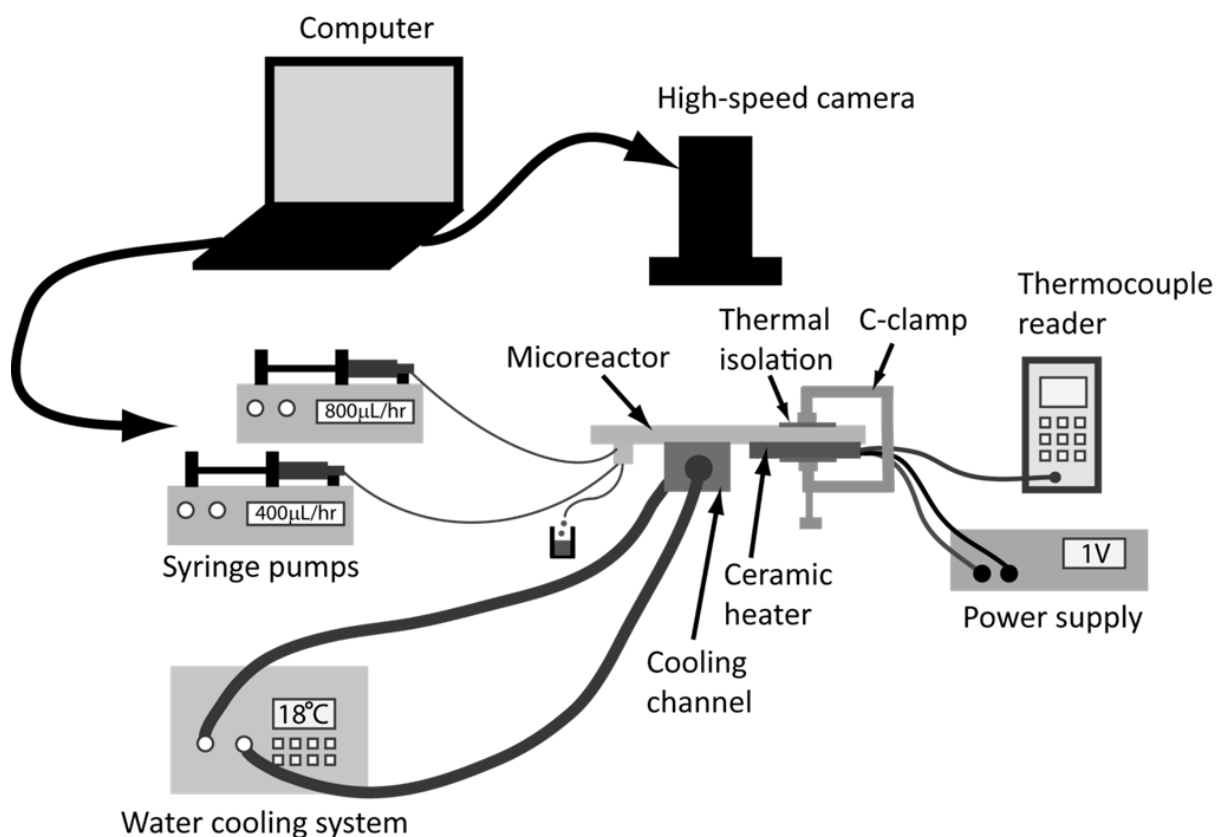
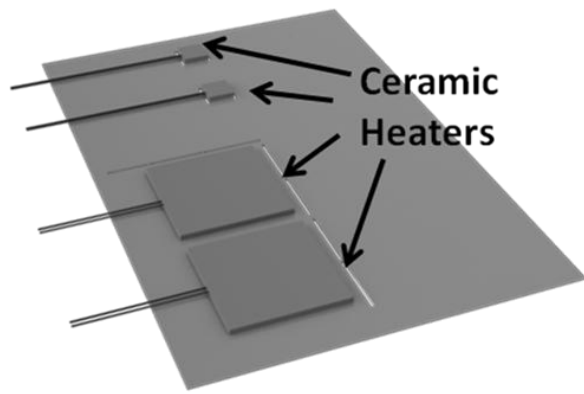


Figure S2. Schematic of the experimental set-up for nanoparticle synthesis.



(A)



(B)

Figure S3. Schematic of the heating and cooling elements.